

A B S T R A C T

A METHOD OF FABRICATING POLYCRYSTALLINE SILICON PLATES

5 The invention relates to a method of fabricating at
least one polycrystalline silicon plate (68, 70) with one
(64, 66) of its two faces presenting predetermined
relief, in which method a layer of polycrystalline
silicon (60, 62) is deposited on at least one (56, 58) of
10 the two faces of a support (50). The method comprises
the steps of embossing said face (52, 54) of the support
(50) to impart thereto a shape that is complementary to
said relief; depositing said polycrystalline silicon
layer (60, 62) on said embossed face (56, 58) of the
15 support (50), the surface (64 or 66) of said
polycrystalline silicon layer situated in contact with
said embossed face (56 or 58) then taking on the shape of
said relief; and eliminating said support in order to
obtain said polycrystalline silicon plate (68 or 70).
20 The invention is applicable to fabricating solar cells.

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